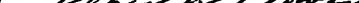


Complete if Known	
Application Number	10/849,617
Filing Date	May 20, 2004
First Named Inventor	Adam Saxler
Group Art Unit	2822
Examiner Name	Michael S. ... K. DUONG
Attorney Docket Number	5308-413

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Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T
KBD	5.	International Search Report corresponding to PCT/US2005/004039, mailed June 30, 2005.	

Examiner Signature		Date Considered	4/5/2006
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Sheet

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of

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Application Number	10/849,617
Filing Date	May 20, 2004
First Named Inventor	Adam Saxler
Group Art Unit	2822
Examiner Name	Amr Zarebian
Attorney Docket Number	5308-413

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John T. Pray

4/5/2006

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Substitute form 1449A/PTO

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

Sheet	1	of	3
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Complete if Known

Application Number	10/849,617
Filing Date	May 20, 2004
First Named Inventor	Saxler et al.
Group Art Unit	2822
Examiner Name	Amir Zarebian
Attorney Docket Number	5308-413

U.S. PATENTS AND PATENT PUBLICATIONS

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FOREIGN PATENT DOCUMENTS

[illegible]

OTHER NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T
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Examiner Signature


Date Considered

4/5/2006

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Application Number	10/849,617
		Filing Date	May 20, 2004
		First Named Inventor	Saxler et al.
		Group Art Unit	2822
		Examiner Name	Abdul Zafar Khan
(use as many sheets as necessary)		Attorney Docket Number	5308-413
Sheet	2	of	3

OTHER NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T
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	36.	United States Patent Application entitled "Methods of Fabricating Nitride-Based Transistors with a Cap Layer and a Recessed Gate," Serial No. 10/897,726, filed July 23, 2004 (Attorney Docket No. 5308-392).	
	37.	United States Patent Application entitled "High Power Density and/or Linearity Transistors," Serial No. 11/005,107, filed December 6, 2004 (Attorney Docket No. 5308-511).	
	38.	United States Patent Application entitled "Field Effect Transistors (FETs) Having Multi-Watt Output Power at Millimeter-Wave Frequencies," Serial No. 11/005,423, filed December 6, 2004 (Attorney Docket No. 5308-512).	
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✓	41.	United States Patent Application entitled "Binary Group III-Nitride Based High Electron Mobility Transistors and Methods of Fabricating Same," Serial No. 11/118,675, filed April 29, 2005 (Attorney Docket No. 5308-544).	

Examiner Signature		Date Considered	4/5/2006
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Substitute form 1449A/PTO		Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Application Number	10/849,617
		Filing Date	May 20, 2004
		First Named Inventor	Saxler et al.
		Group Art Unit	2822
		Examiner Name	<i>Robert Zafarian</i>
Sheet 3 of 3	Attorney Docket Number	5308-413	

OTHER NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T
<i>KBD</i>	42.	United States Patent Application entitled "Composite Substrates of Conductive And Insulating or Semi-Insulating Group III-Nitrides For Group III-Nitride Devices," Serial No. 11/103,127, filed April 11, 2005 (Attorney Docket No. 5308-551).	
	43.	United States Patent Application entitled "Thick Semi-Insulating or Insulating Epitaxial Gallium Nitride Layers and Devices Incorporating Same," Serial No. 11/103,117, filed April 11, 2005 (Attorney Docket No. 5308-553).	
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Examiner Signature	<i>John T. Dwyer</i>	Date Considered	<i>4/5/2006</i>
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



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Sheet	A1	of	A1
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Sheet	A1	of	A1
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Application Number	10/849,617
Filing Date	May 20, 2004
First Named Inventor	Saxler
Group Art Unit	2511
Examiner Name	John A. Saxon
Attorney Docket Number	5308-413

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John W. Brown

4/5/2006

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First Named Inventor

Group Art Unit

Examiner Name

Attorney Docket Number

10/849,617

May 20, 2004

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U.S. PATENTS AND PATENT PUBLICATIONS

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FOREIGN PATENT DOCUMENTS

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OTHER NON PATENT LITERATURE DOCUMENTS

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Examiner Signature

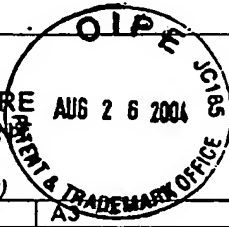
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Substitute form 1449A/PTO

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(use as many sheets as necessary)

Sheet **A1** of **A3**

Complete if Known

Application Number	10/849,617
Filing Date	May 20, 2004
First Named Inventor	Saxler
Group Art Unit	2654
Examiner Name	Bob Assigned
Attorney Docket Number	5308-413

U.S. PATENTS AND PATENT PUBLICATIONS

Examiner Initials*	Cite No.	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY
		Number	Kind Code (if known)		
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Date Considered

4/15/2006

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		Filing Date	May 20, 2004
		First Named Inventor	Saxler
		Group Art Unit	2811
		Examiner Name	Tee Be Assigned
Sheet A2 of A3	Attorney Docket Number	5308-392	

FOREIGN PATENT DOCUMENTS							
Examiner Initials*	Cite No.	Foreign Patent Document			Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	T
		Office	Number	Kind Code (if known)			
KBD	44.	PCT	WO 03/049193	A1	Cree, Inc.	06-12-2003	
	45.	JP	2002016087	A	NEC Corp	01-18-2002	Abstract
	46.	JP	2001230407	A	Matsushita Electric Industrial Co. Ltd.	08-24-2001	Abstract
	47.	PCT	WO 01/57929	A1	Cree Lighting Company	08-09-2001	
	48.	JP	10-050982		Nippon Telegraph & Telephone Corp.	02-20-1998	Abstract
	49.	PCT	WO 93/23877	A1	Massachusetts Institute of Technology	11-25-1993	
	50.	EP	0 563 847	A2	Matsushita Electric Industrial Co., Ltd.	10-06-1993	

OTHER NON PATENT LITERATURE DOCUMENTS					
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Examiner Signature		Date Considered			

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Application Number	10/849,617		
		Filing Date	May 20, 2004		
		First Named Inventor	Saxler		
		Group Art Unit	2874		
		Examiner Name	TO BE Assigned		
Sheet	A3	of	A3	Attorney Docket Number	5308-392

OTHER NON PATENT LITERATURE DOCUMENTS			
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	82.	United States Patent Application entitled "Nitride Heterojunction Transistors Having Charge-Transfer Induced Energy Barriers and Methods of Fabricating the Same," Serial No. 10/772,882, filed February 5, 2004 (Attorney Docket No. 5308-389.)	
	83.	United States Patent Application entitled "Nitride-Based Transistors with a Protective Layer and a Low-Damage Recess and Methods of Fabrication Thereof," Serial No. 10/758,871, filed January 16, 2004 (Attorney Docket No. 5308-291).	
	84.	United States Patent Application entitled "Nitride-Based Transistors and Methods of Fabrication Thereof Using Non-Etched Contact Recesses," Serial No. 10/617,843, filed July 11, 2003 (Attorney Docket No. 5308-248).	
	85.	United States Patent Application entitled "Semiconductor Devices Having a Hybrid Channel Layer, Current Aperture Transistors and Methods of Fabricating the Same," Serial No. 10/849,589, filed May 20, 2004 (Attorney Docket No. 5308-412).	
	86.	United States Patent Application entitled "Methods of Fabricating Nitride-Based Transistors with a Cap Layer and a Recessed Gate," filed July 23, 2004 (Attorney Docket No. 5308-392).	
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	88.	United States Patent Application entitled, "Silicon Carbide on Diamond Substrates and Related Devices and Methods," (Cree Docket No. P0387).	

Examiner Signature	<i>John H. Jones</i>	Date Considered	4/5/2006
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.